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By: *Linda E. Hastings*

LINDA E. HASTINGS

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Attorney Docket No.: NEKW14.868

23/E
2/14
3/6/01
NE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

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TECHNOLOGY CENTER 1700

February 27, 2001

Assistant Commissioner for Patents
BOX NON-FEE AMENDMENT
Washington, D.C. 20231

*OK to
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JIC 3/2001*

RESPONSE TO OFFICE ACTION

S I R :

In response to the Office Action mailed on November 29, 2000, the period for responding thereto having been set to expire on February 28, 2001, please amend the above-captioned application as follows:

E